

Fig.1

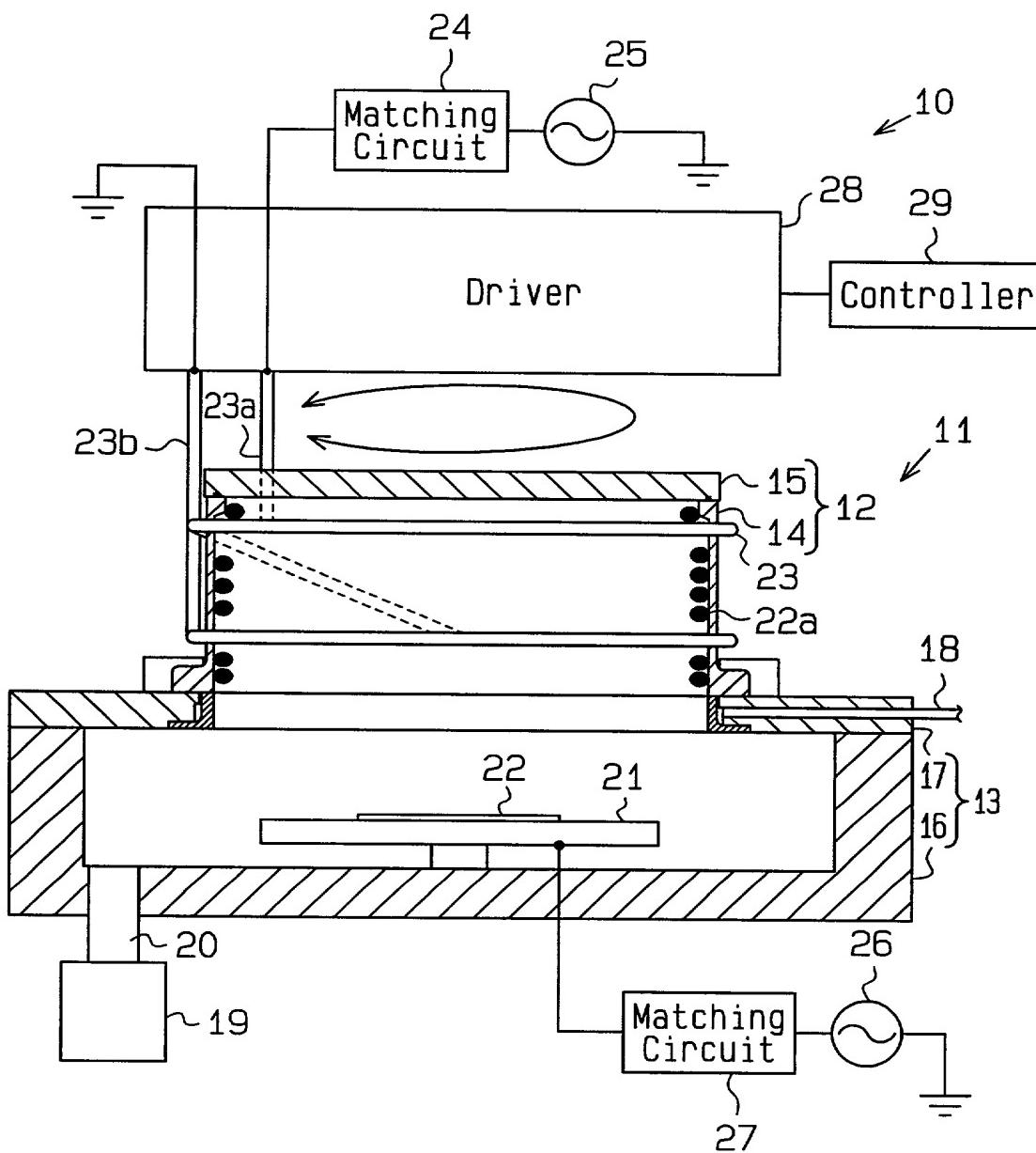


Fig.2a

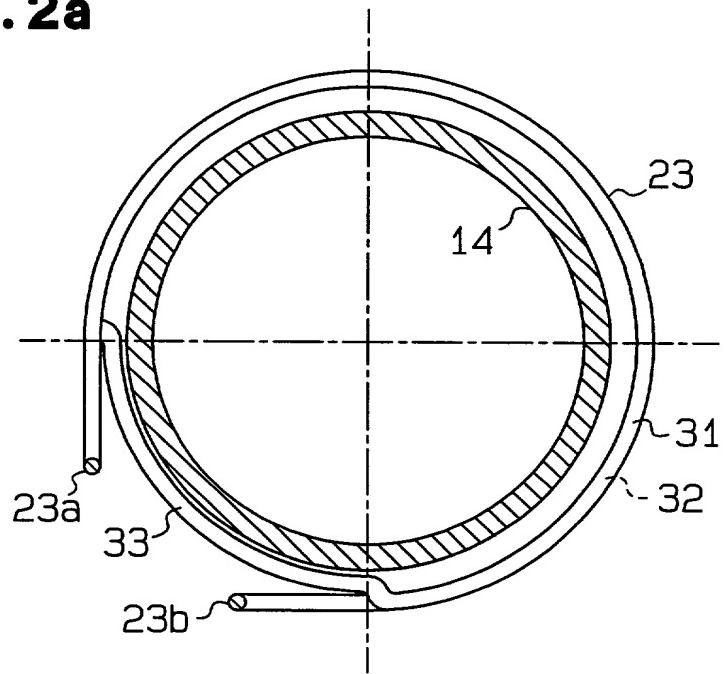


Fig.2b

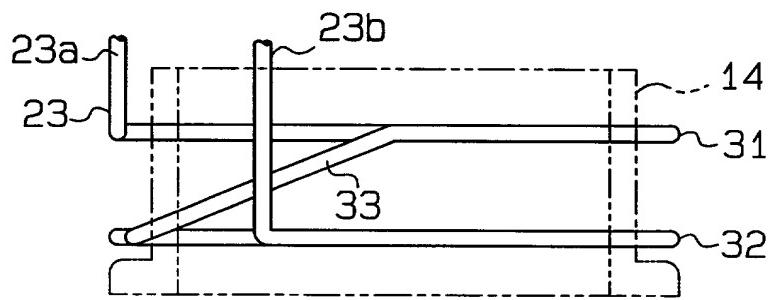
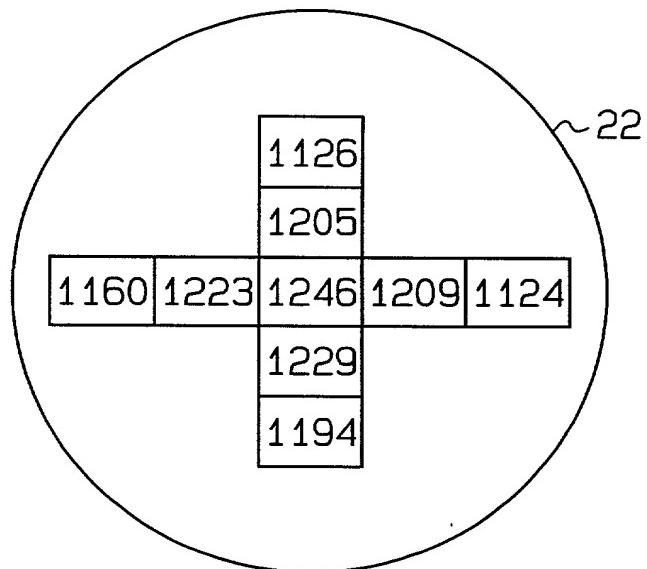


Fig.3a



**Fig.3b
(Prior Art)**

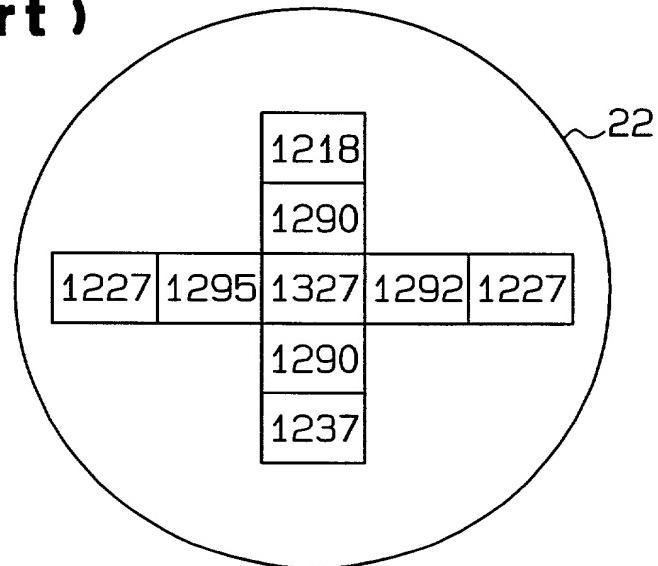


Fig.4

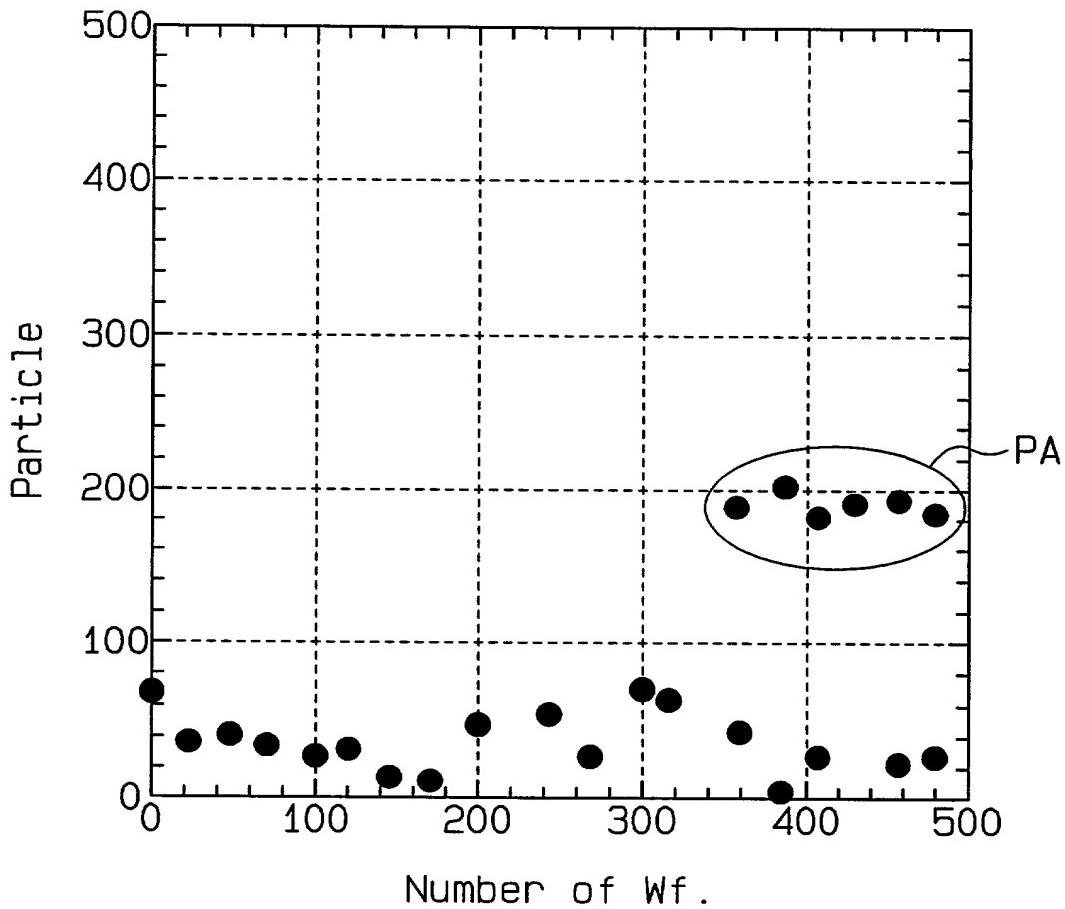


Fig.5

Numbers of wafers rotation	Rotation rate (rpm)	Number of processed wafers	Particle size	Initial particle number	Particle number after processing	Difference	TOTAL
0	0	25	S	19	26	+7	+31
			SM	1	12	+11	
			M	0	13	+13	
			L	0	0	0	
		100	SM	10	18	+8	+17
			SM	2	6	+4	
			M	3	8	+5	
			SM	0	0	0	
		25	S	24	59	+35	+43
			SM	3	5	+2	
			M	6	12	+6	
			L	0	0	0	
Approx. 3.75	Approx. 0.52	100	S	15	15	0	+13
			SM	2	6	+4	
			M	6	15	+9	
			L	0	0	0	
		150	S	21	5	-16	-18
			SM	0	3	+3	
			M	7	2	-5	
			L	0	0	0	
		25	S	2	23	+21	+33
			SM	1	8	+7	
			M	8	13	+5	
			L	0	0	0	
Approx. 37	Approx. 0.054	100	S	37	13	-24	-37
			SM	15	6	-9	
			M	15	10	-5	
			L	0	1	+1	
		25	S	8	26	+18	+29
			SM	4	7	+3	
			M	13	21	+8	
			L	0	0	0	
		100	S	22	19	+3	+10
			SM	1	8	+7	
			M	3	9	+6	
			L	0	0	0	
		150	S	12	19	+7	+12
			SM	0	3	+3	
			M	3	5	+2	
			L	0	0	0	

Fig.6

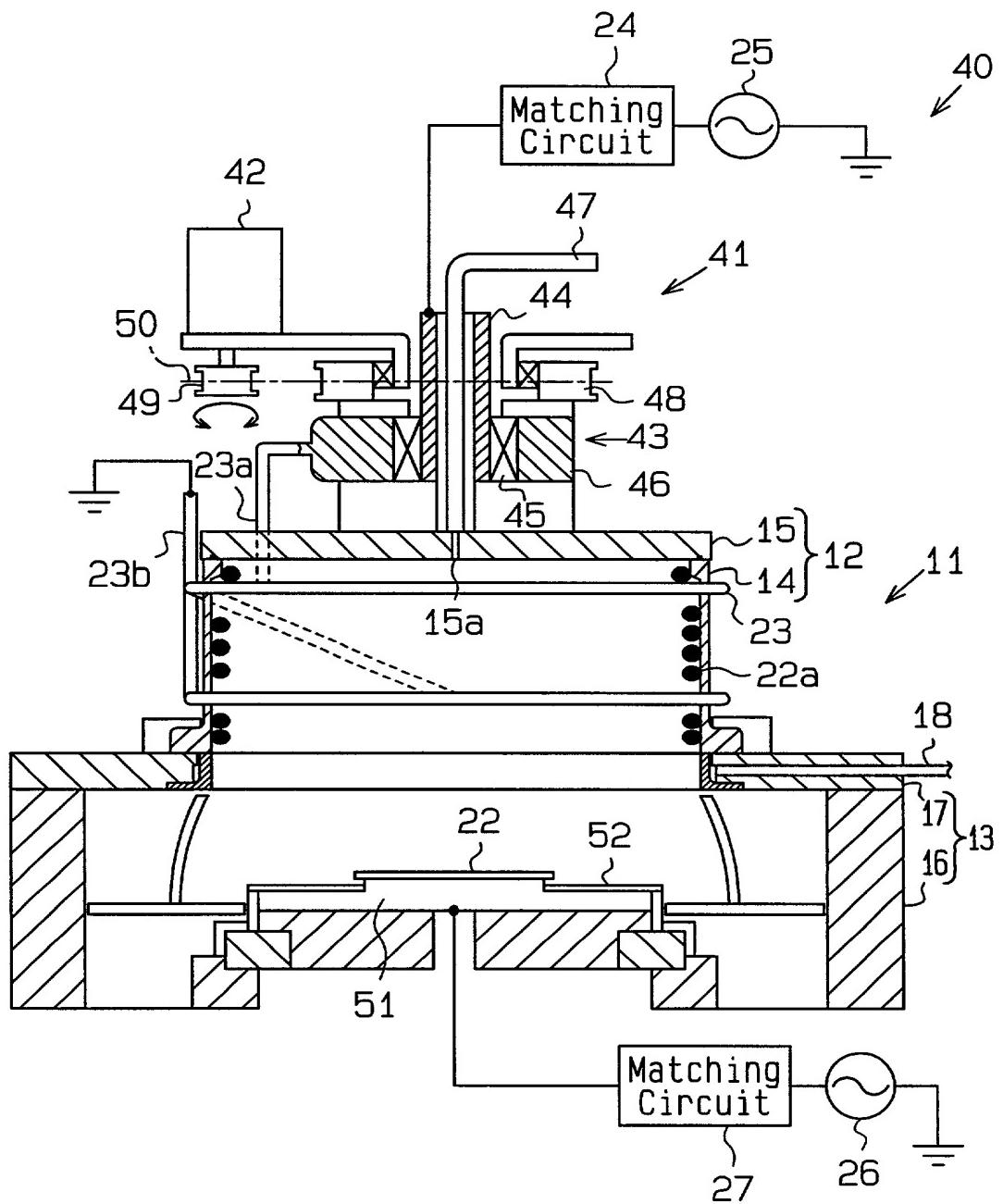


Fig.7a

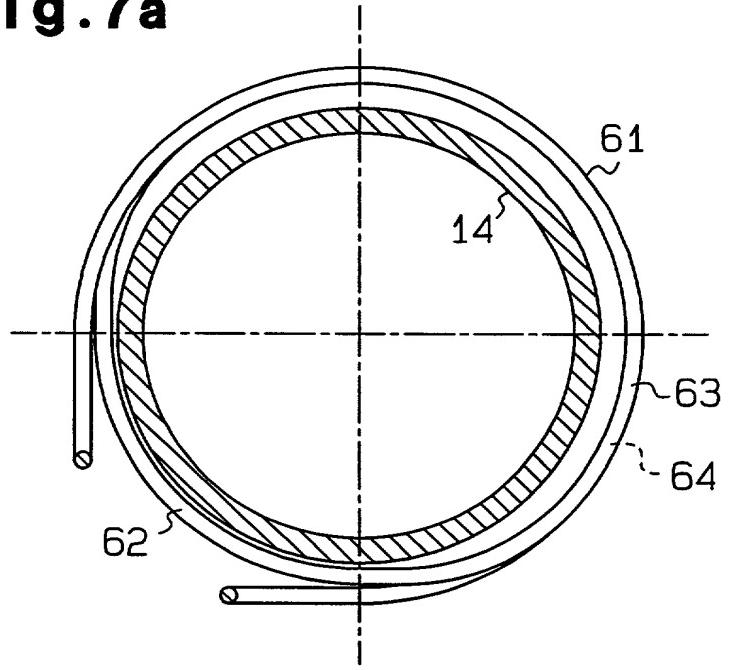


Fig.7b

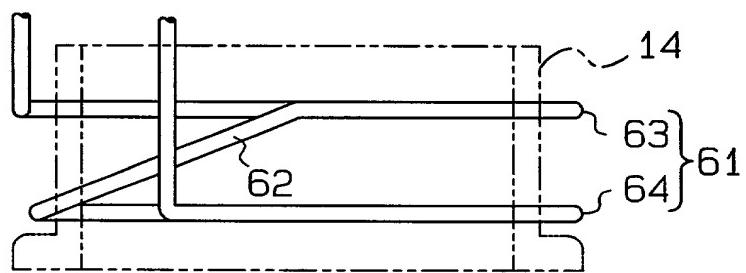


Fig.8a

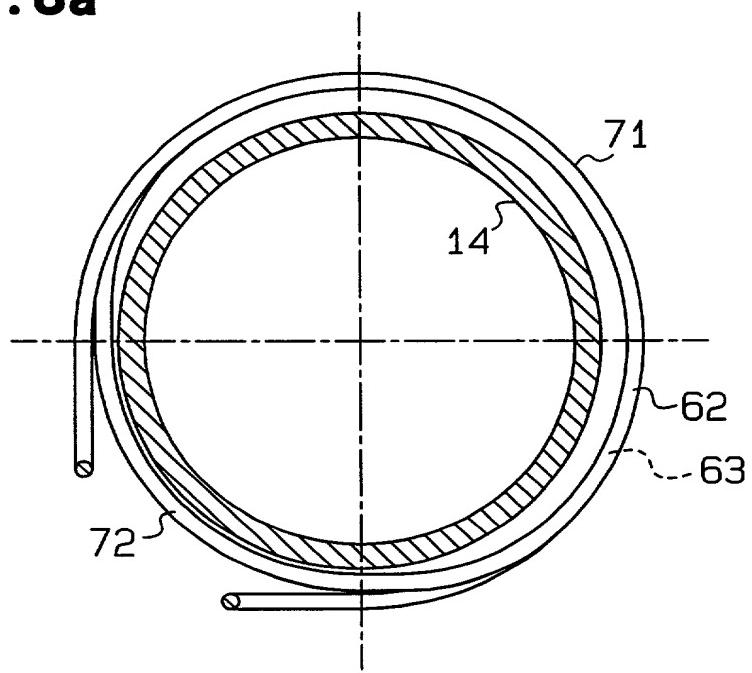


Fig.8b

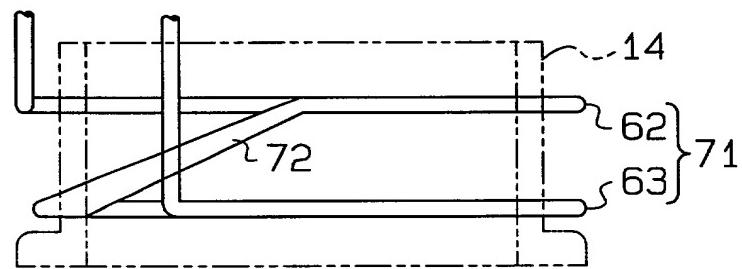


Fig.9a

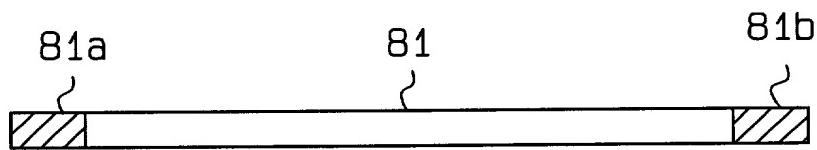


Fig.9b

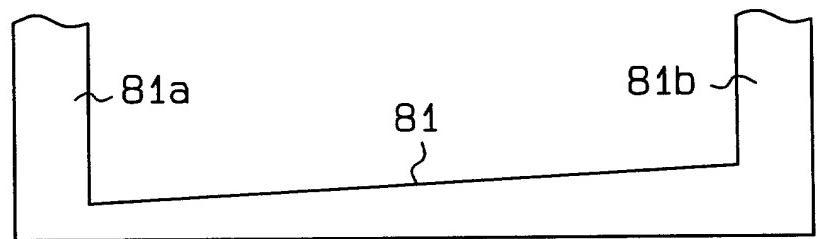


Fig.10a

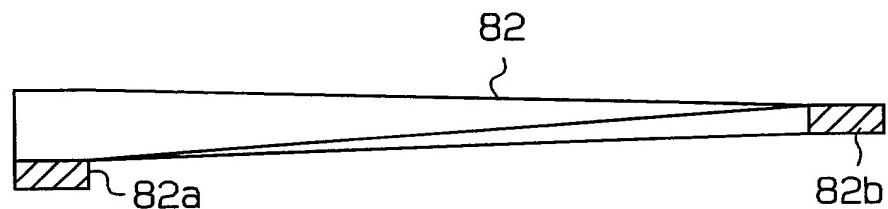


Fig.10b

